5th Online WORKSHOP EUV-FEL



JST (UTC + 9)**PST (UTC - 8)** CET (UTC + 1)Japan Time California Time Central Europe Time

22/Jan./2021 21/Jan./2021 22/Jan./2022

Session Chair 12:00 19:00 04:00

12:30-12:40 19:30-19:40 4:30-4:40 Hiroshi Kawata Opening remarks

4:40-5:20 Hidemi Ishiuchi 12:40-13:20 19:40-20:20 key note lecture

Fundamental Research to Solve the EUV Technical Issues and Future Prospect for EUVL toward Advanced Devices Fabrication

5:20-5:50 Ryoichi Hajima 13:20-13:50 20:20-20:50 Invited speaker(1)

Compact Storage Ring FEL: a kW-scale EUV lithography source.

5:50-6:20 Ryoichi Hajima 13:50-14:20 20:50-21:20 Invited speaker(2)

Construction and commissioning of cERL IR-FEL toward realization of the EUV-FEL

14:20-14:50 21:20-21:50 6:20-6:50 Ryoichi Hajima Invited speaker(3)

Industrial application of accelerator: Medical RI production

BreakBreak

7:20-7:50 Soichi Inoue Invited speaker(4)

Driving Moore's Law through Process and Packaging Innovations

Soichi Inoue 7.50-8.20 *Invited speaker*(5) 15:50-16:20

EUV Lithography as key scaling enabler for logic and memory

Soichi Inoue 8:20-8:50 Invited speaker(6) 16:20-16:50 23:20-23:50

High-NA EUV Lithography exposure tool for EUV roadmap extension

16:50-17:00

Hiroshi Kawata 8:50-9:00 23:50-24:00

Photo-session

Closing address &

Sunao Ishihara

Representative of EUV-FEL Light Source Study Group for Industrialization

Takeo Watanabe

Center for EUVL, Director, Laboratory of Advanced Science and Technology for Industry, Dean, University of Hyogo

Rod Loewen

Lyncean Technologies, Inc., (CTO)

Norio Nakamura

Kentaro Harada

Naoki Kitano Intel K K

Geert Vandenberghe

Jan van Schoot, Jos Benschop, Sjoerd Lok, Eelco van Setten, Ruben Maas, Kars Troost, Jo Finders, Paul Graeupner

ASML

TBA